	Application No.	Applicant(s)	
Notice of Allowability	10/646,080	HALLIYAL et al.	
	Examiner	Art Unit	
	Lee Calvin	2825	
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308. 1. This communication is responsive to			
2. X The allowed claim(s) is/are <u>1-20</u> .			
3. The drawings filed on 22 August 2003 are accepted by the	Examiner.		
 4.			
Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 2 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	5. ☐ Notice of Informal P6. ☐ Interview SummaryPaper No./Mail Date	atent Application (PTC (PTO-413), te ment/Comment	,

Application No: 10/646,080

Docket No: G0463A

Page 2

HALLIYAL et al.

OFFICE ACTION

Allowable Subject Matter

Claims 1-20 are allowed. Following is the reason for allowance:

Haukka et al (US 2002/0115252) discloses forming a layer comprising a high-K dielectric material sandwiched between top and first aluminum oxide layers [Abstract]. Gregor et al (US 6,008,091) discloses forming a tantalum pentoxide sandwiched between first and second silicon dioxide layers. However, neither Haukka et al nor Gregor et al teaches or suggests, inter alia, forming a modified ONO structure with the steps of depositing a layer comprising a high-K dielectric material on a first oxide layer and forming a top oxide layer on the layer comprising a high-K dielectric material.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance.

Contact Information

Any inquiry concerning this communication from the Examiner should be directed to *Calvin Lee* at (571) 272-1896 from 7:00 to 17:00 (Monday-Thursday). If attempts to reach the examiner by telephone are unsuccessful, Art Unit 2825's Supervisory Patent Examiner *Matthew Smith* can be reached at (571) 272-1907.

Any inquiry relating to the status of this application should be directed to the Group receptionist whose telephone number is (703) 305-3900. The fax phones are (703) 872-9318 for regular communications and (703) 872-9319 for After-Final communications.

MATTHEW SMITH
SUPERVISORY PATENT EXAMINER
TECHNOLOGY CENTER 2800

4

March 22, 2004